Applicant(s)
OH ET AL.
Art Unit
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the correspondence address—this application. If not included nication will be mailed in due course. THIS ubject to withdrawal from issue at the initiative
r (f). n No in this national stage application from the
a reply complying with the requirements
MINER'S AMENDMENT or NOTICE OF declaration is deficient.
(PTO-948) attached
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e drawings in the front (not the back) of R 1.121(d).
RIAL must be submitted. Note the LOGICAL MATERIAL.
ormal Potent Application (DTO 452)
ormal Patent Application (PTO-152) mmary (PTO-413),
Mail Date Amendment/Comment
Statement of Reasons for Allowance

Application/Control Number: 10/624,723

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DETAILED ACTION

Response to Amendment

The Amendment, filed on February 13, 2006, has been entered and acknowledged by the Examiner.

Claims 1-23 are pending in the instant application.

Allowable Subject Matter

Claims 1-23 are allowed over the prior art of record.

The following is an examiner's statement of reasons for allowance:

Regarding claim 1, the references of the Prior Art of record fails to teach or suggest the combination of the limitations as set forth in claim 1, and specifically comprising the limitation of a first substrate, at least one gate electrode formed in a predetermined pattern on the first substrate, a plurality of cathode electrodes formed on the first substrate in a predetermined pattern, at least one first insulation layer formed between the at least one gate electrode and the plurality of cathode electrodes, and at least one emitter mounted within an opening of the cathode electrode.

Regarding claims 2-12, claims 2-12 are allowable for the reasons given in claim 1 because of their dependency status from claim 1.

Regarding claim 13, the references of the Prior Art of record fails to teach or suggest the combination of the limitations as set forth in claim 13, and specifically comprising the limitation of a first substrate, a plurality of gate electrodes formed in a predetermined pattern on the first substrate, plurality of cathode electrodes formed on the first substrate in a predetermined pattern, the cathode electrodes forming intersection regions with the gate electrodes corresponding to pixel regions, at least one first insulation layer between the at least one gate electrode and the plurality of cathode

elements, an emitter mounted within openings of the cathode electrodes formed in the intersection regions.

Regarding claims 14-20, claims 14-20 are allowable for the reasons given in claim 13 because of their dependency status from claim 13.

Regarding claim 21, the references of the Prior Art of record fails to teach or suggest the combination of the limitations as set forth in claim 21, and specifically comprising the limitation of a first substrate, at least one gate electrode formed in a predetermined gate electrode pattern on the first substrate, a plurality of cathode electrodes formed on the first substrate in a predetermined pattern, at least one first insulation layer formed between the at least one gate electrode and the plurality of cathode electrodes, emitters electrically contacting the cathode electrodes.

Regarding claims 22 and 23, claims 22 and 23 are allowable for the reasons given in claim 21 because of their dependency status from claim 21.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Contact Information

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Mariceli Santiago whose telephone number is (571) 272-2464. The examiner can normally be reached on Monday-Friday from 9:30 AM to 6:00 PM.

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If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nimesh Patel, can be reached on (571) 272-2457. The fax phone number for the organization where this application or proceeding is assigned is (571) 273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Mariceli Santiago Primary Examiner Art Unit 2879